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Recent Results and Future Plans for a 45 Actuator Adaptive X-ray Optics Experiment at the Advanced Light Source

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Recent results and Future Plans for a 45 Actuator Adaptive X-ray Optics Experiment at the Advanced Light Source

Synchrotron Radiation Instrumentation - Focusing & Imaging Optics

July 8, 2015

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LLNL-PRES-674140

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Overview

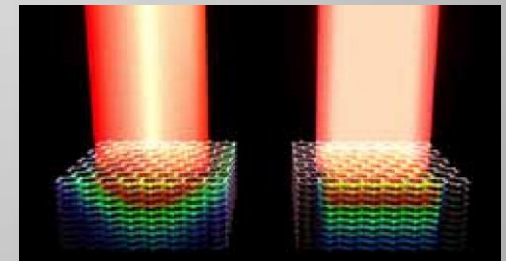
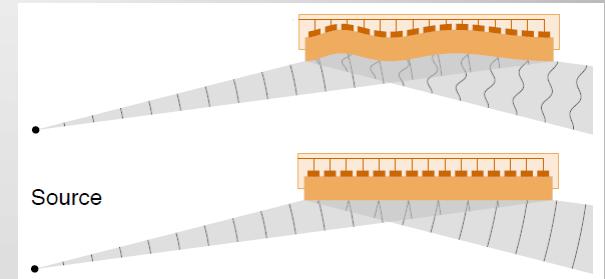
- Introduction
- Progress & status
- Next steps



*See also IWXM 2015 Tuesday 4:30 PM, “**At-wavelength experiments with a 45-cm long X-ray deformable mirror at the ALS**” by Lisa Poyneer*

Adaptive X-ray Optics

- Why adaptive optics?
 - Correct mirror-polishing errors
 - On-demand beam shaping
 - Near real-time dynamic correction
- Why Lawrence Livermore?
 - LLNL visible-light AO expertise
 - LLNL X-ray optic expertise



Rendering by Kwei-Yu Chu

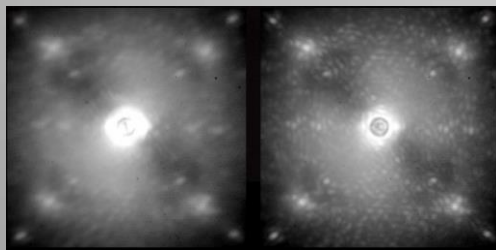
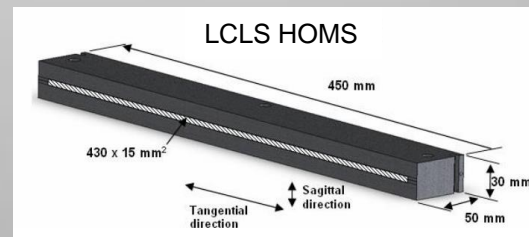


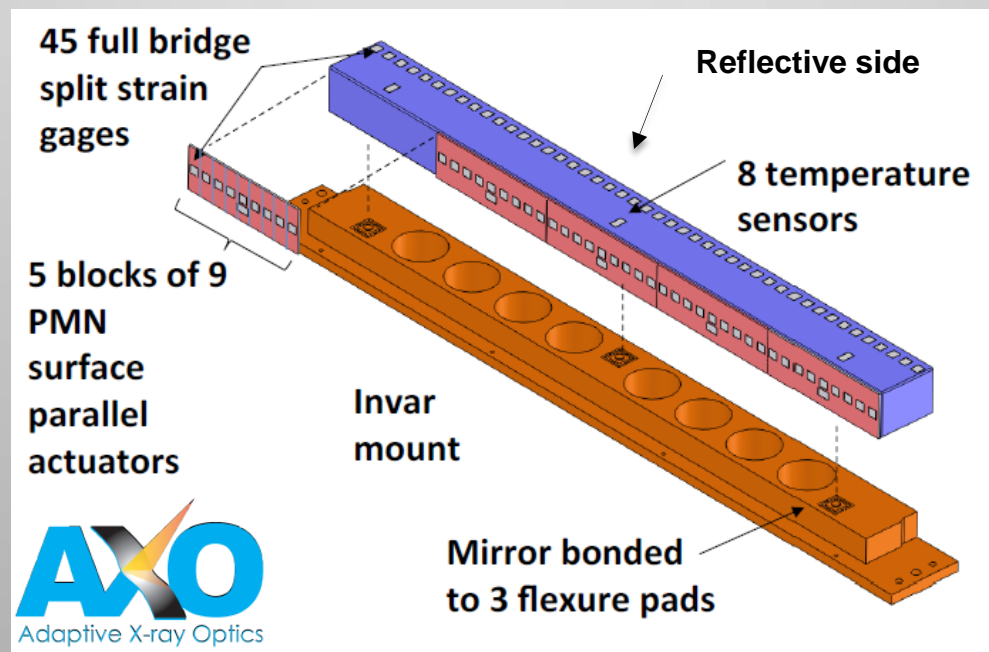
Image credits: GPI team



T. J. McCarville, et al., SPIE Vol. 7077 (2008)

Adaptive X-ray Optics @ LLNL

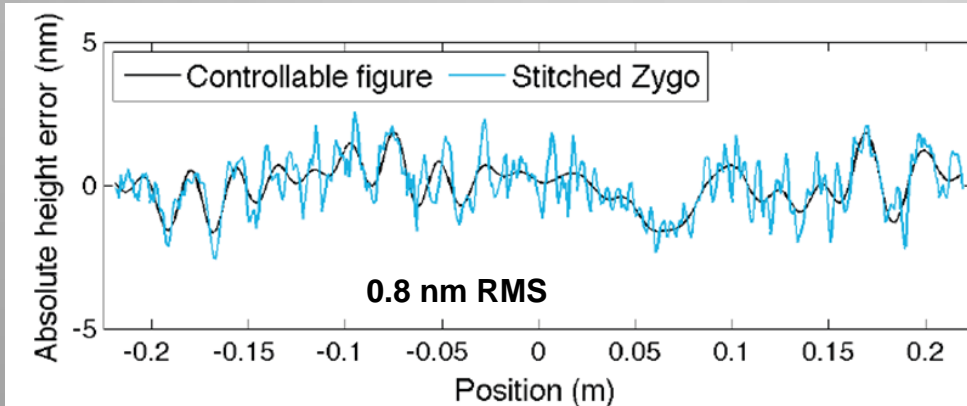
- 45x3x4 cm³ single-crystal silicon substrate
- Developed with Northrop Grumman



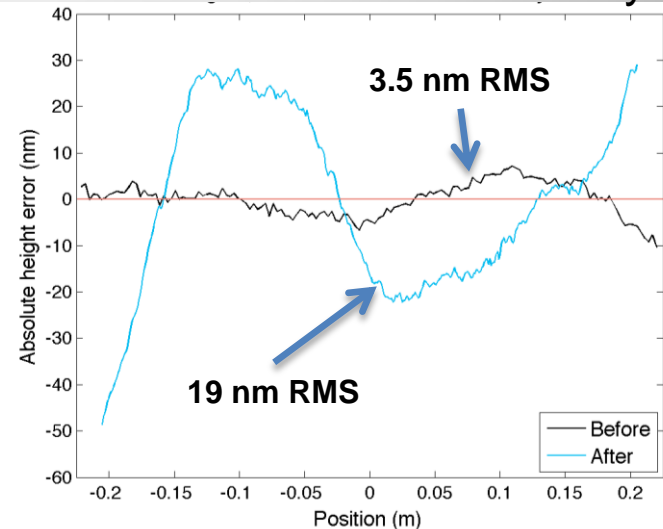
Published results

- HSFR ~ 0.37 nm RMS
- MSFR ~ 0.52 nm RMS
- LSFR (figure error)

After actuation



Before and after assembly



For additional details refer to:

L. A. Poyneer, et. al, Applied Optics Vol. 53, No. 16, pp. 3404-3414 (2014)

&

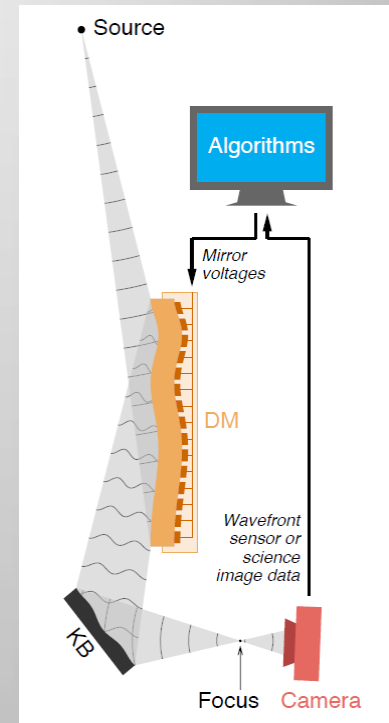
L. A. Poyneer, et. al, Proc. SPIE 9208, 92080F (2014)

Development focus areas of project

- System-level performance
 - Deformable mirror technology
 - Metrology techniques
 - Modeling and simulations

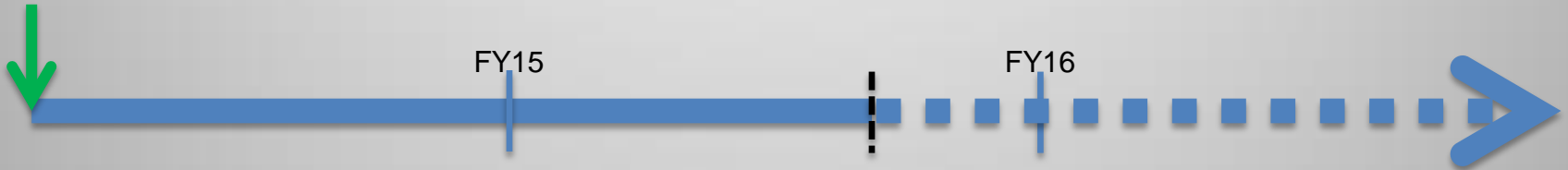


Solid base for next-gen development in partnership with light source



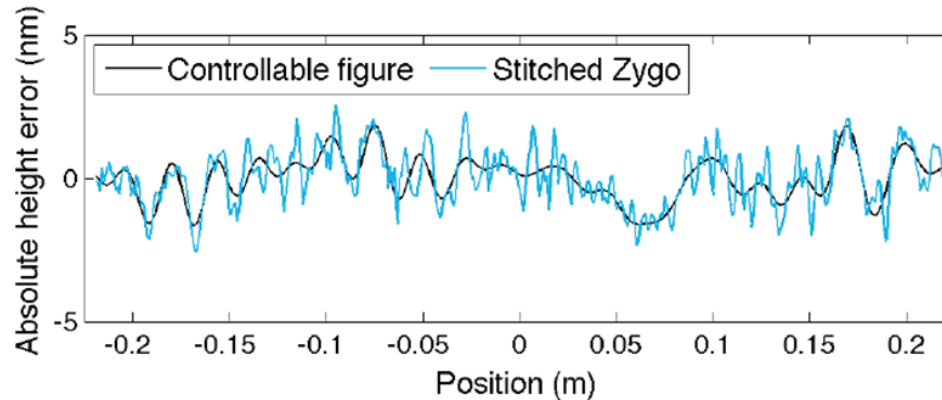
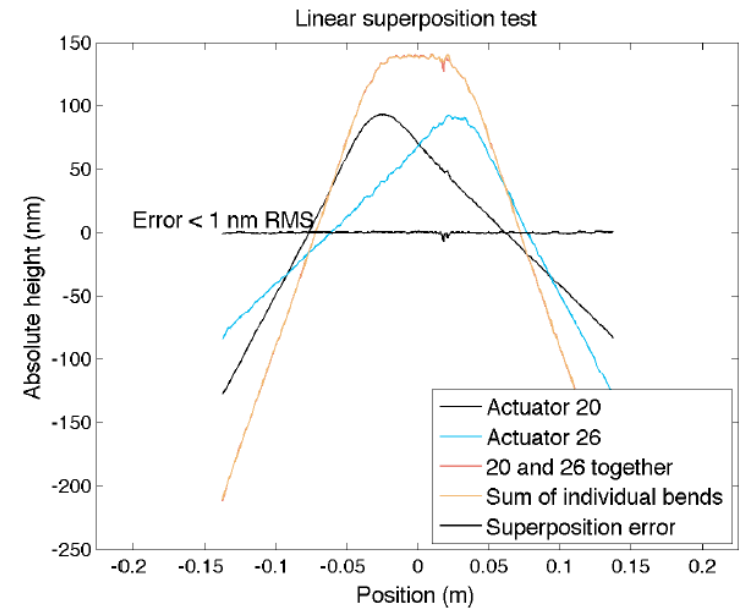
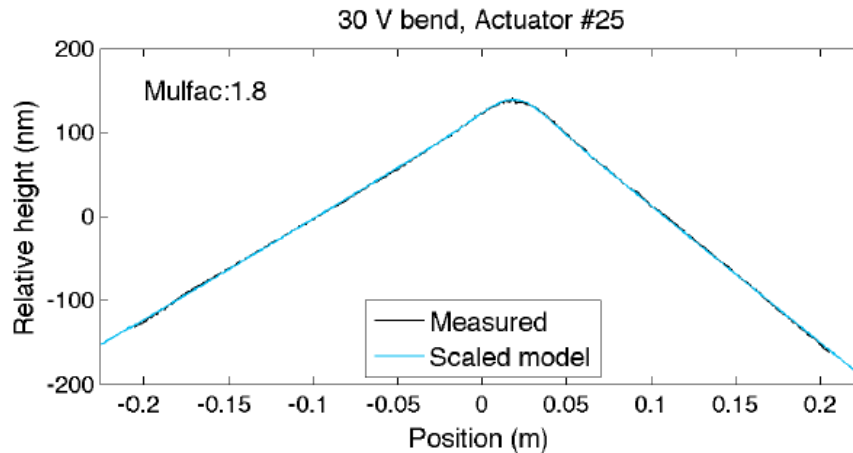
Project timeline

XDM delivery



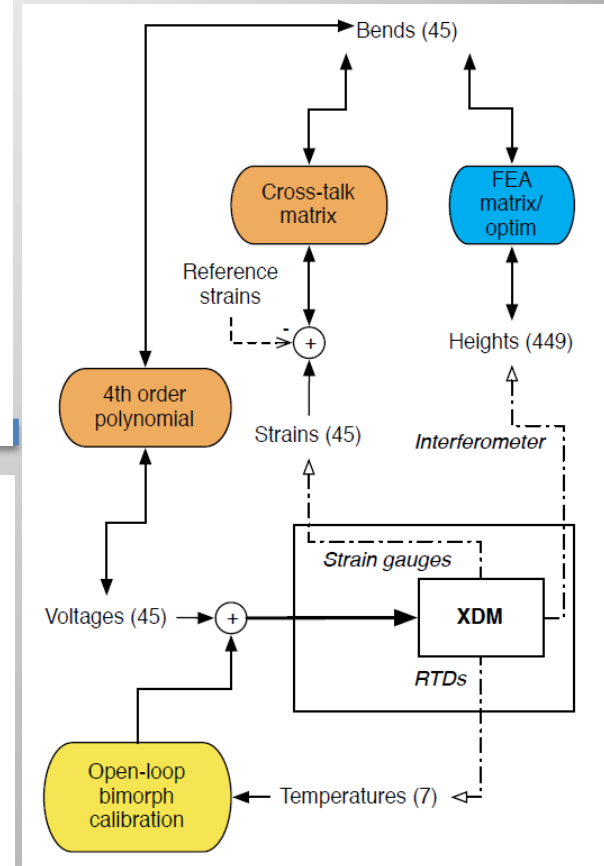
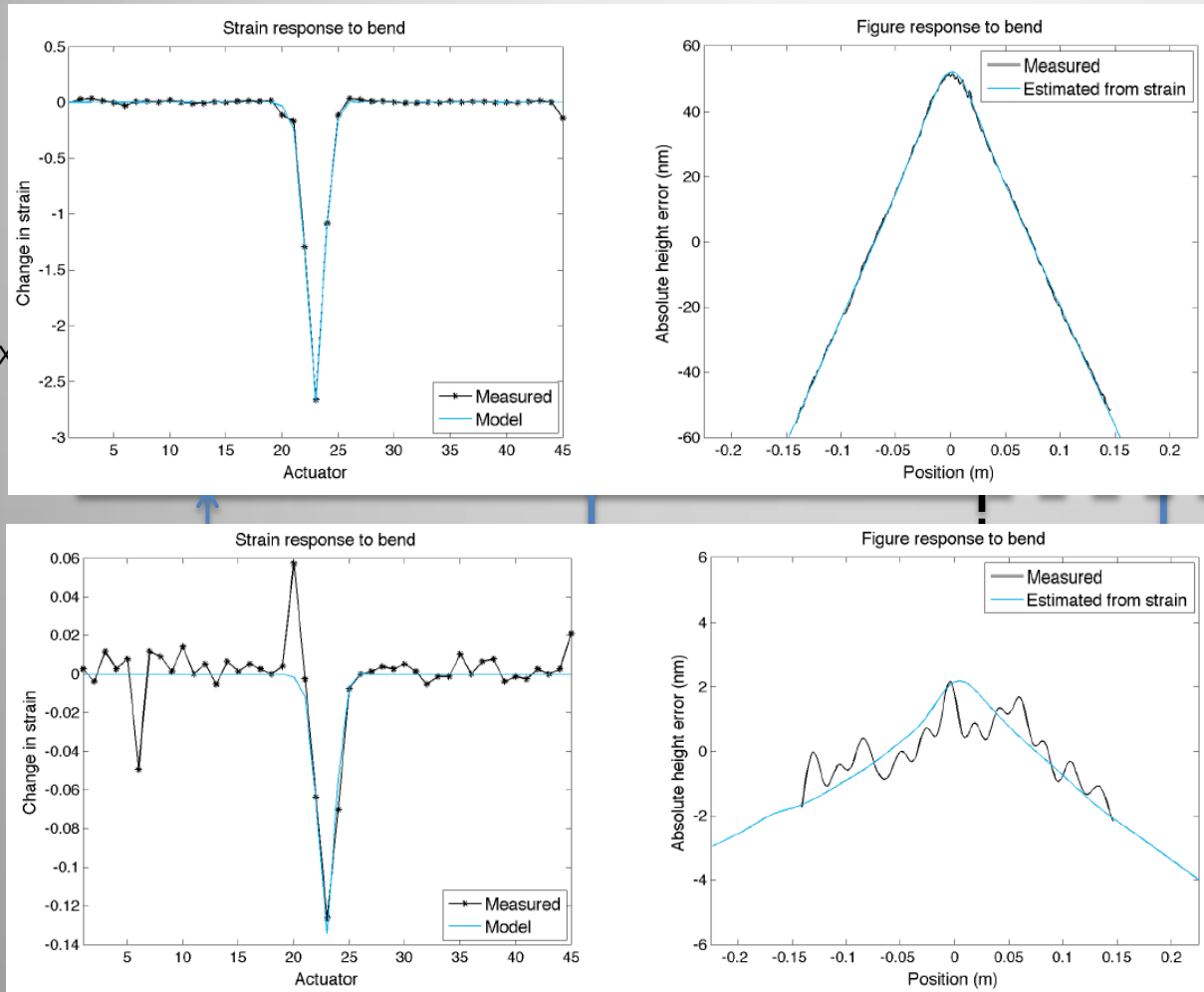
Metrology campaign

XDM d

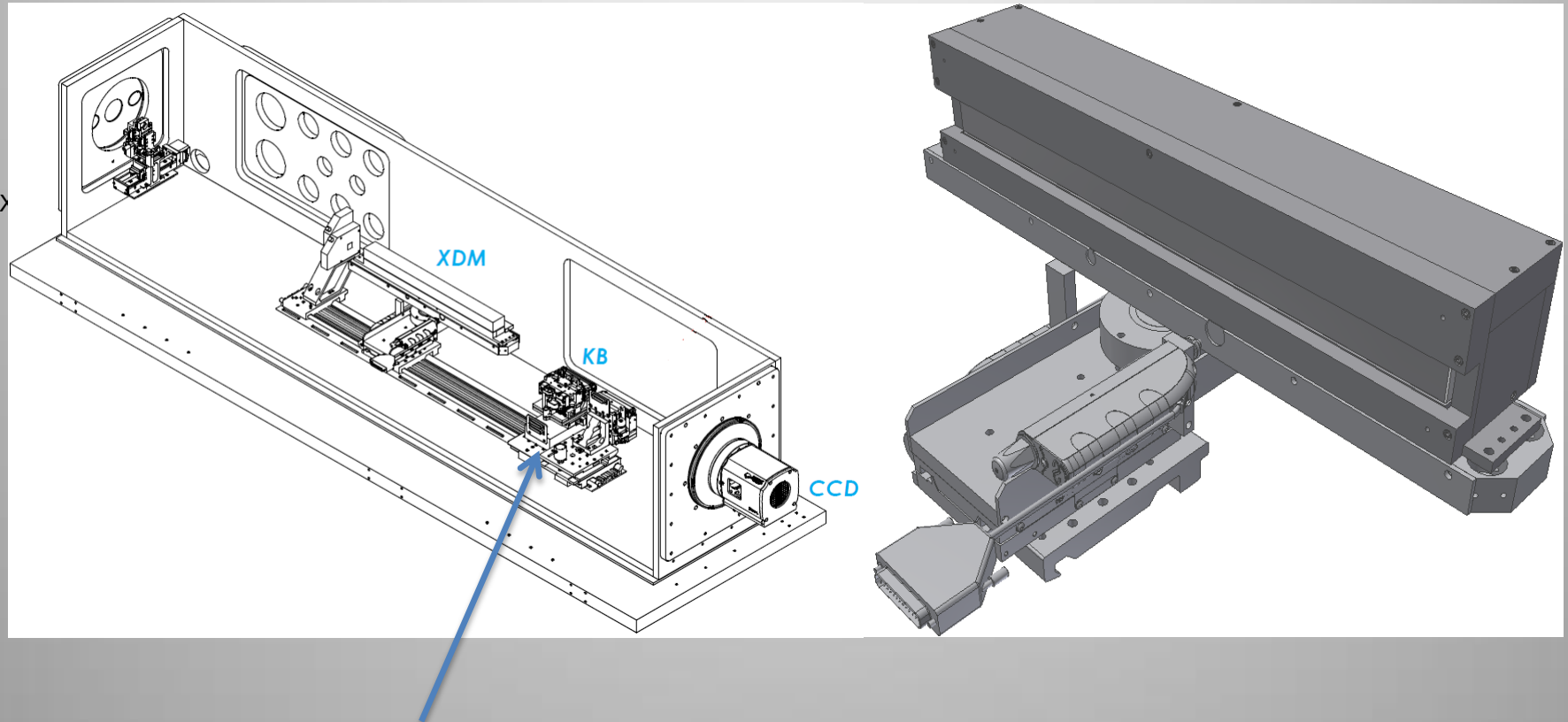


Metrology campaign

In situ metrology campaign

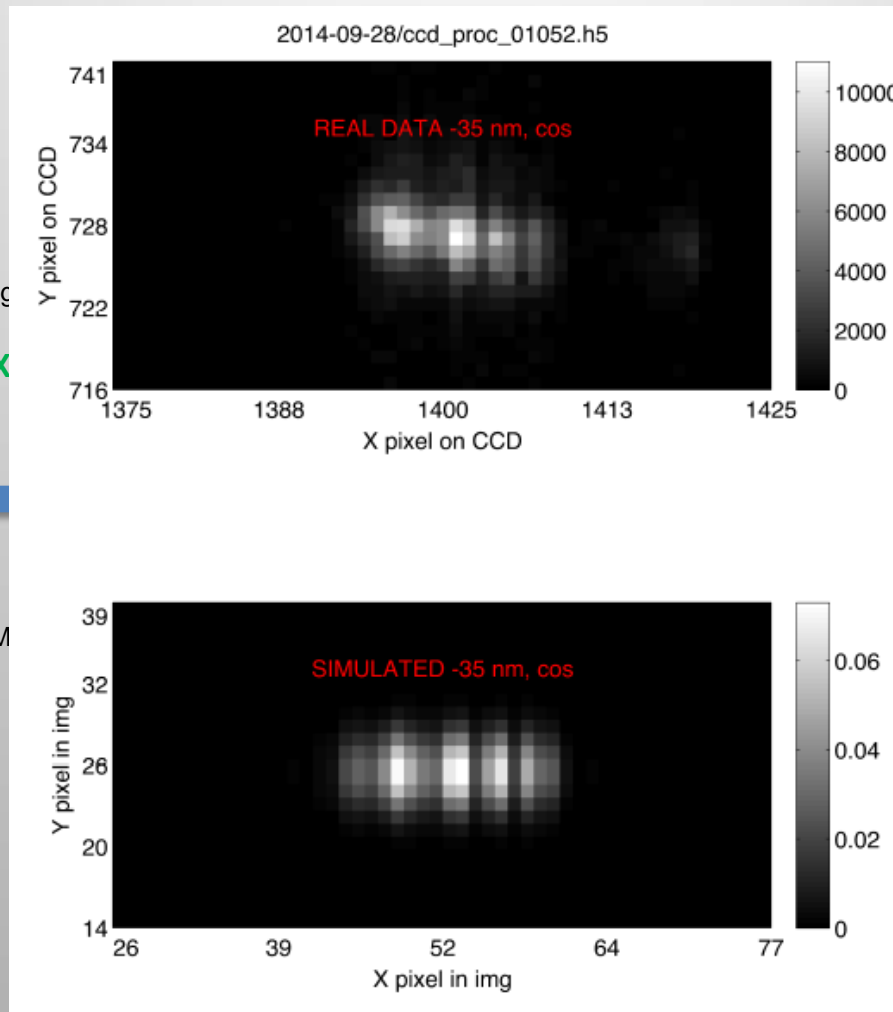
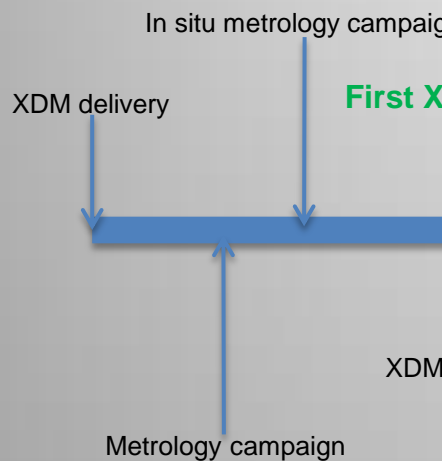


XDM install at ALS 5.3.1

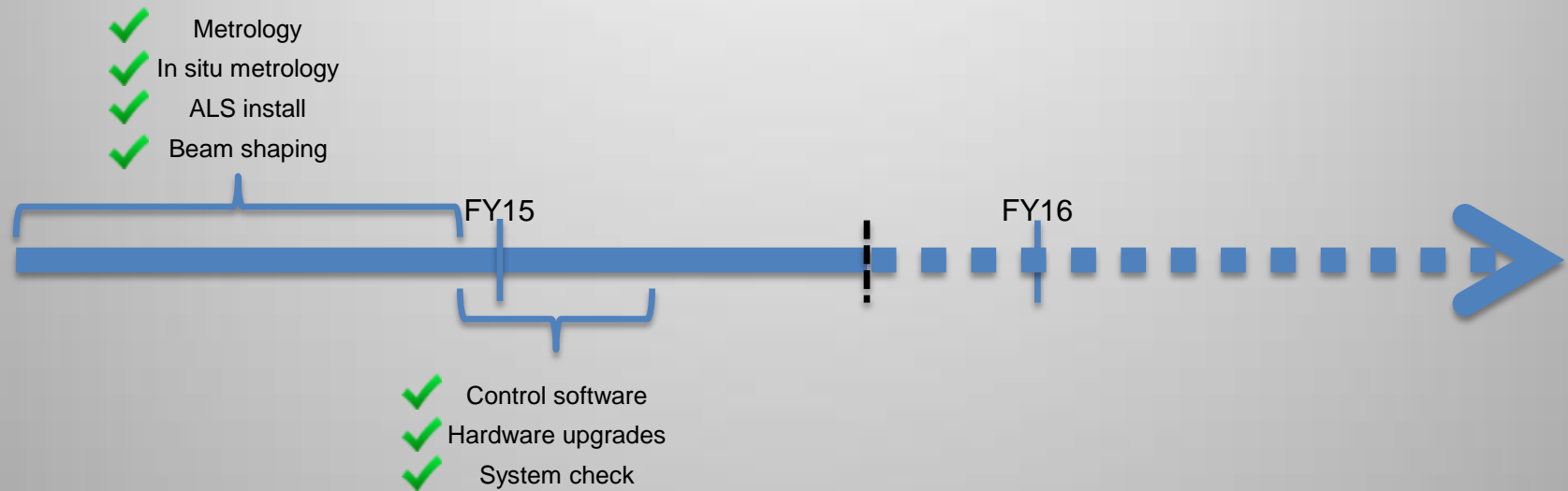


KB reference: S. Yuan, et. al, Proc. SPIE 7801, 78010D (2010)

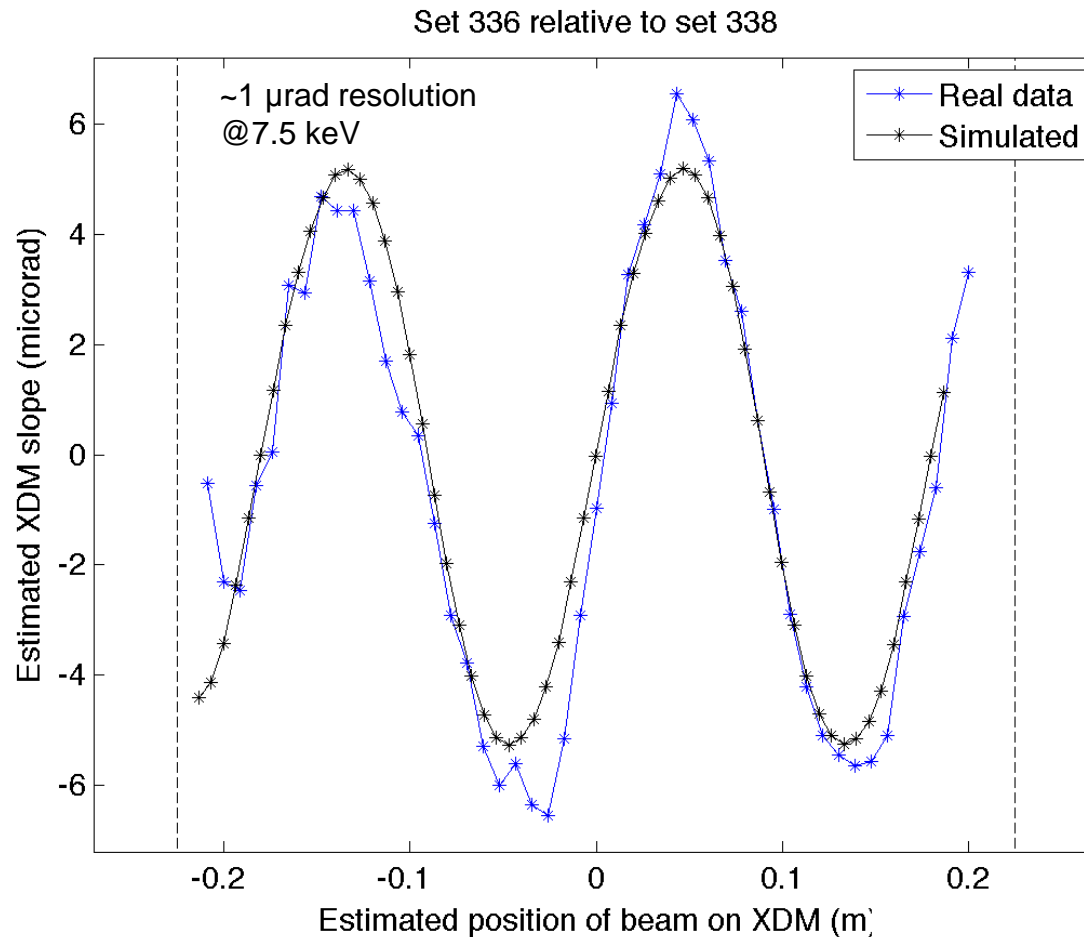
First X-ray beam shaping



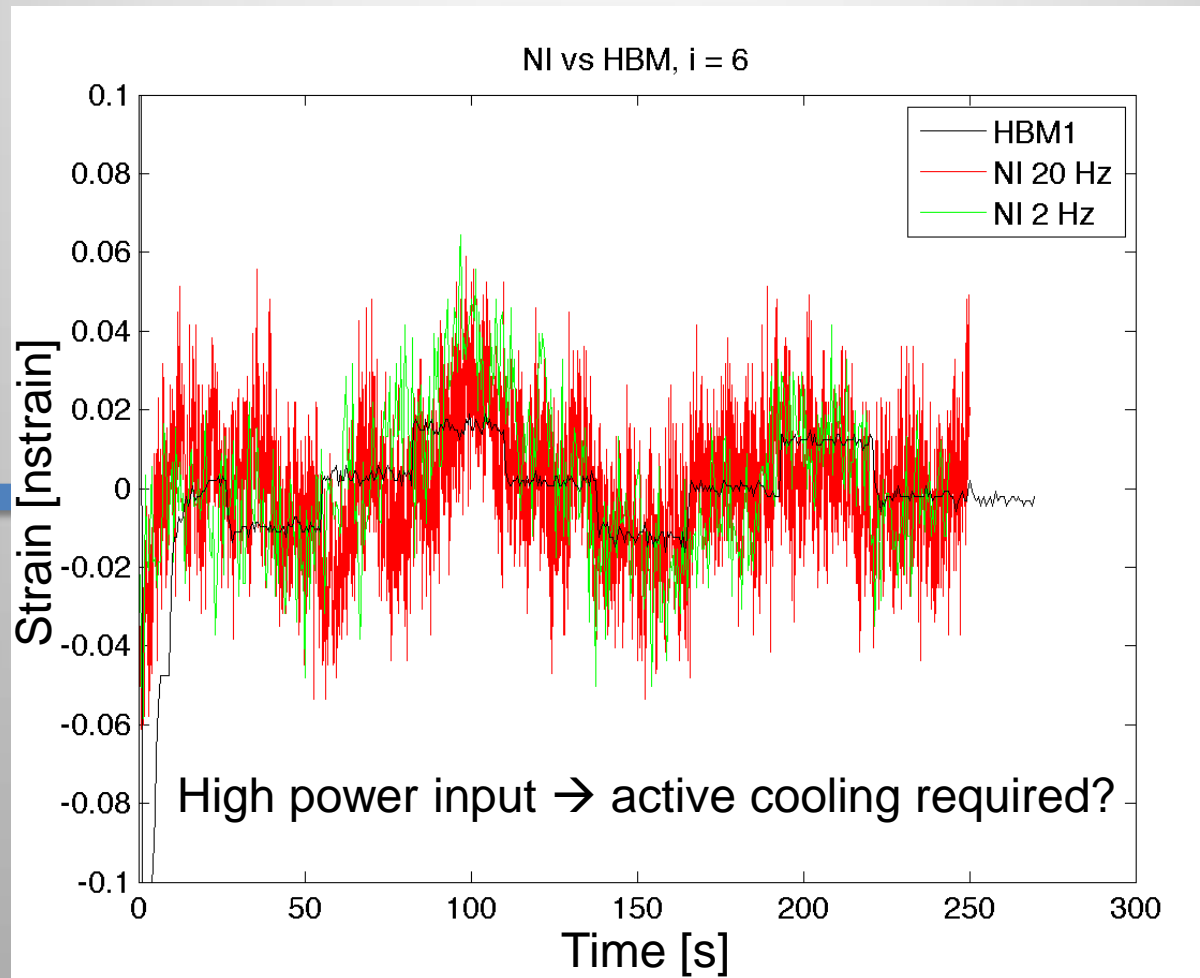
Getting settled in



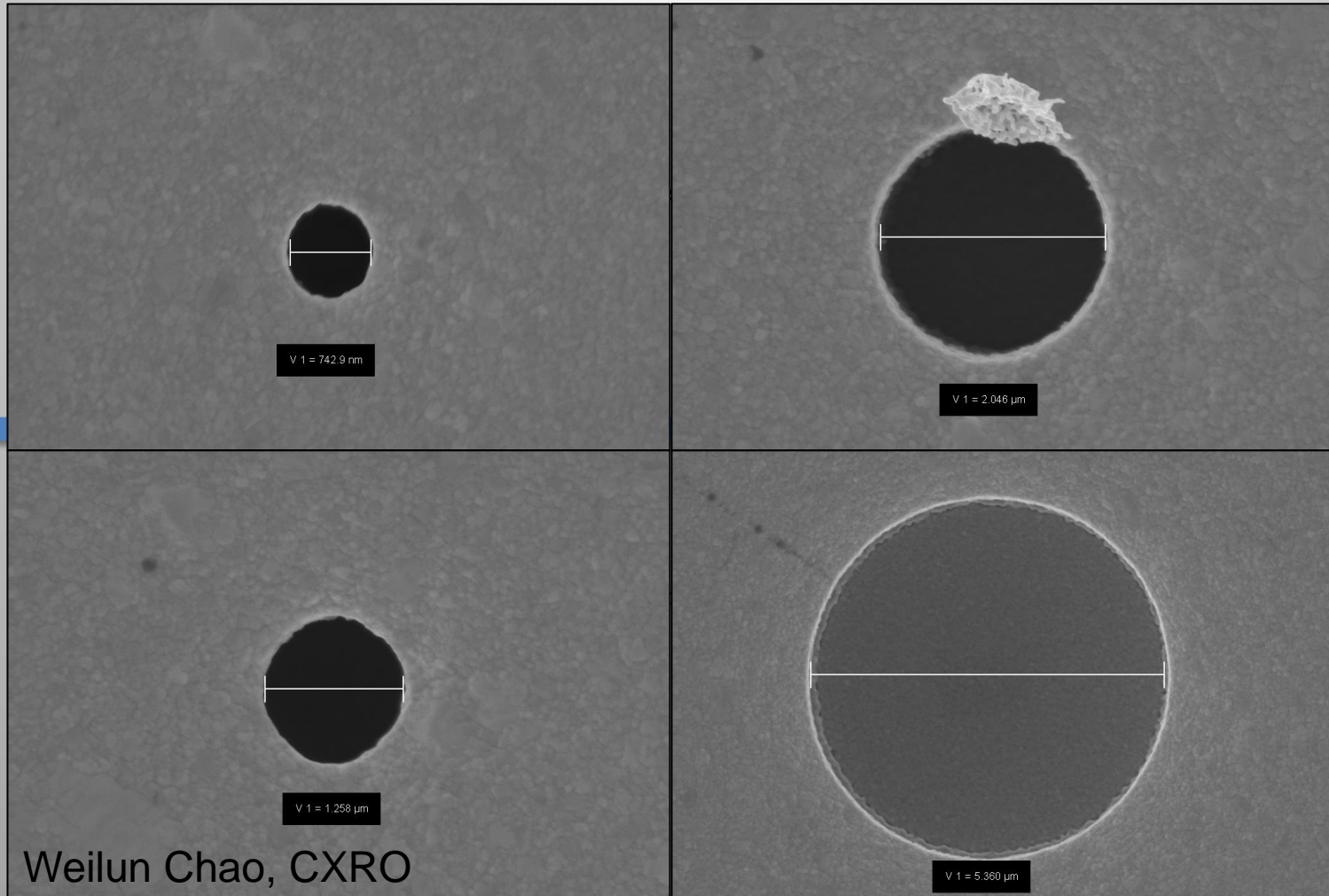
At-wavelength coarse metrology



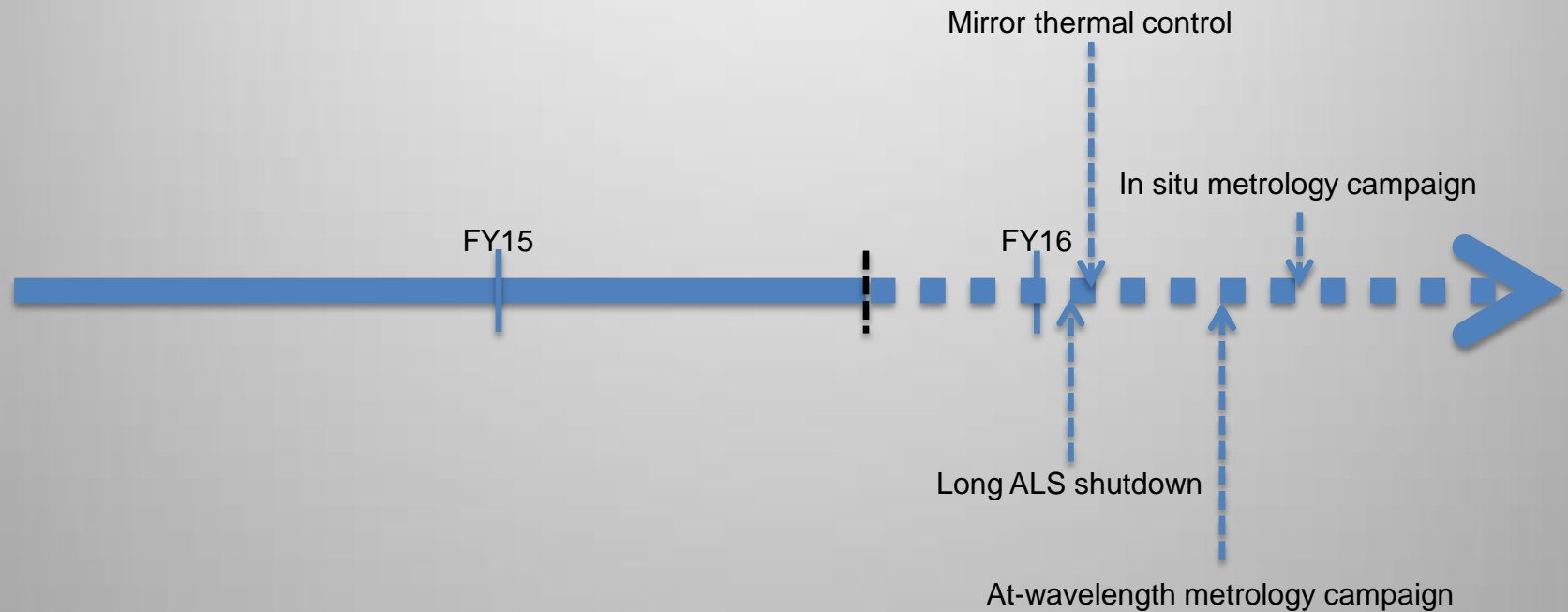
Read-out electronics upgrade



Current work – mono and pinholes



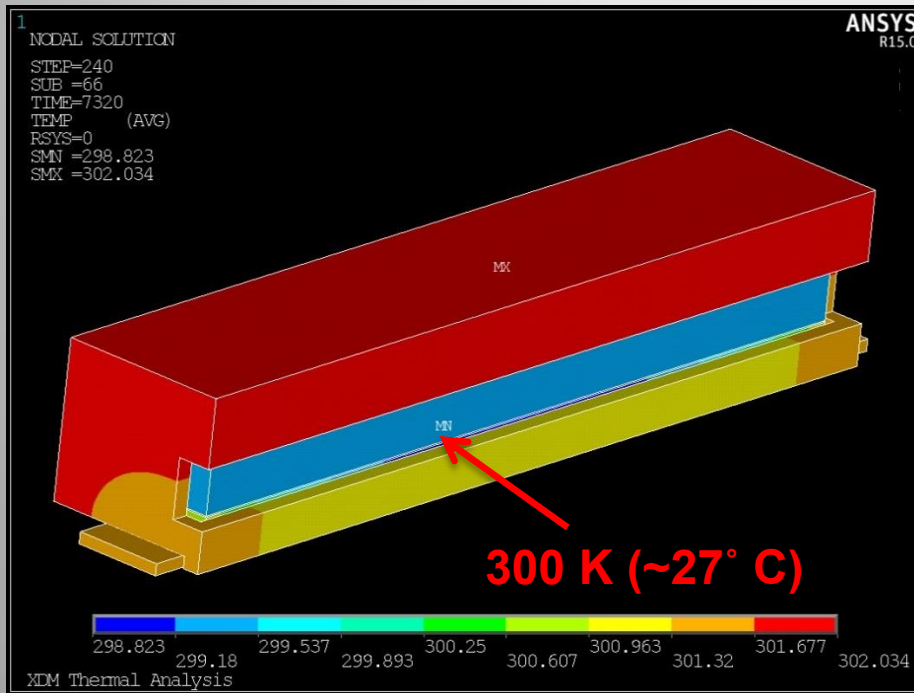
Next steps



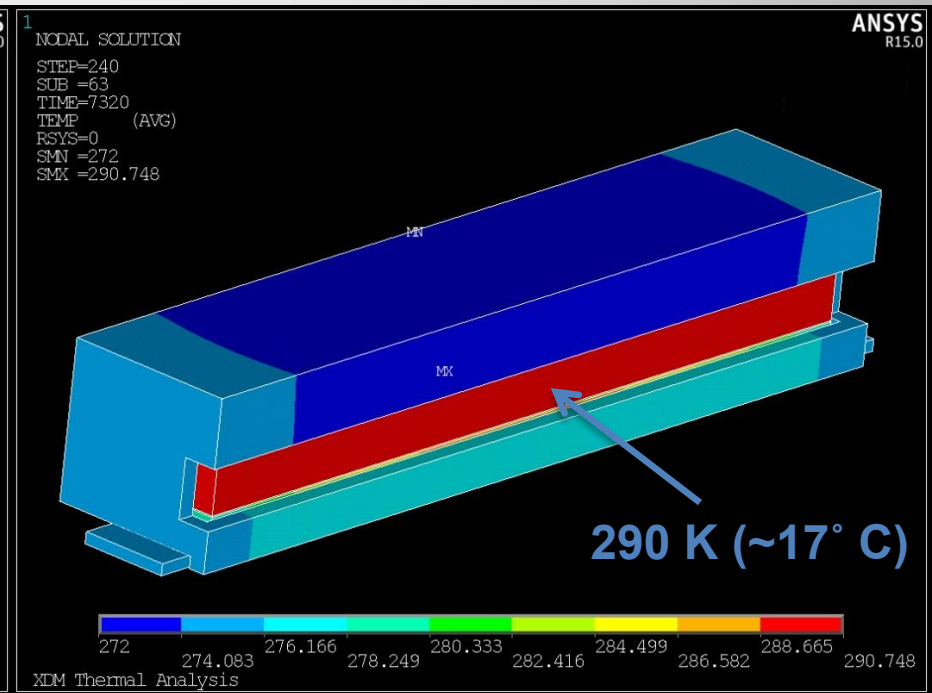
Next steps

- Qualify hardware upgrades
 - Mono, pinholes, support hardware
- Qualify new software
 - New readout electronics, simulation tools
- Finalize alignment and qualification procedures
- Finalize mirror thermal control plans
- Finalize metrology upgrade plans

Mirror thermal control



Climbing quick



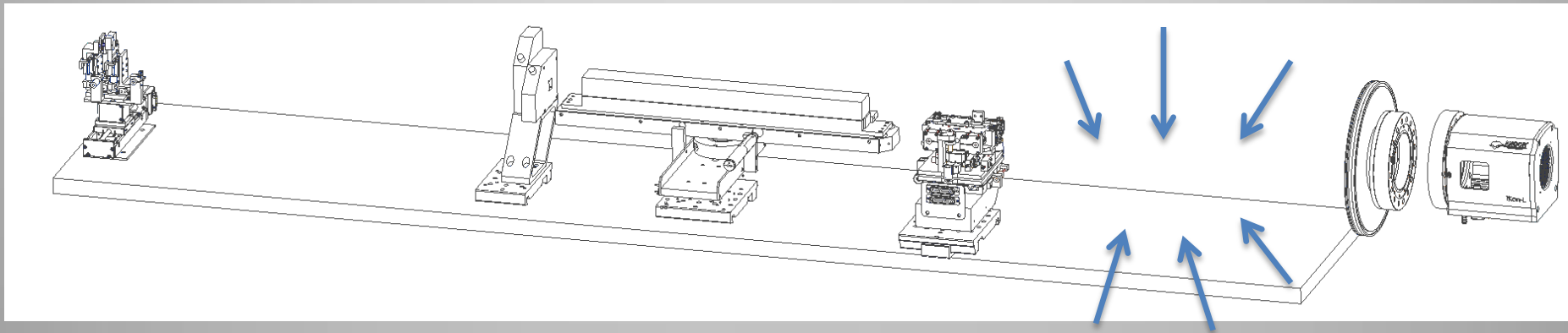
Actively cooled

Metrology status

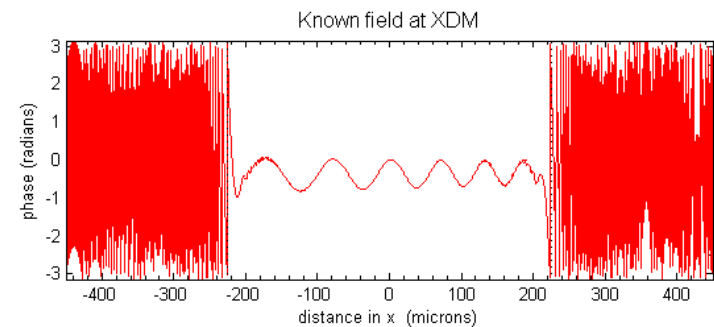
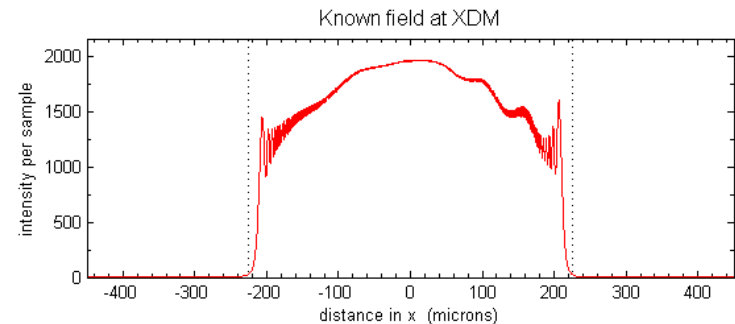
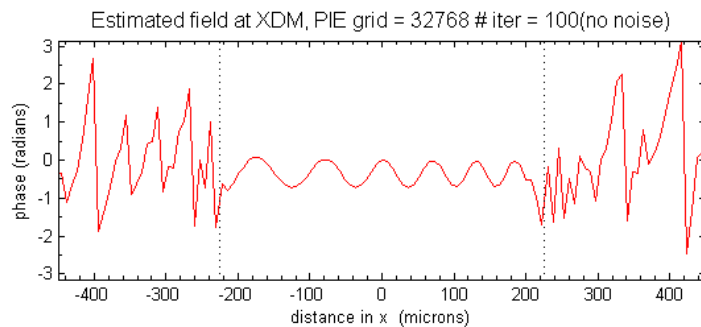
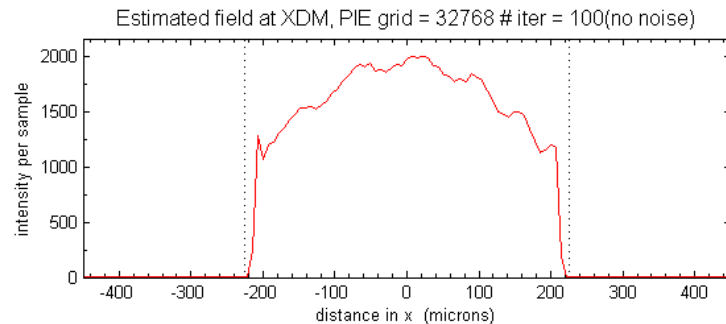
	Visible	“Coarse” at-wavelength	“Fine” at-wavelength	Strain gauges
FY14	Closed-loop < 1 nm	Specify	Identify	Open-loop < 10 nm
FY15	-	Measure ~1 μrad Closed-loop < 1 μrad	Specify	Measure < 5 nm
FY16	-	-	Measure < 1 nm Closed-loop < 1 nm	Closed-loop < 1 nm

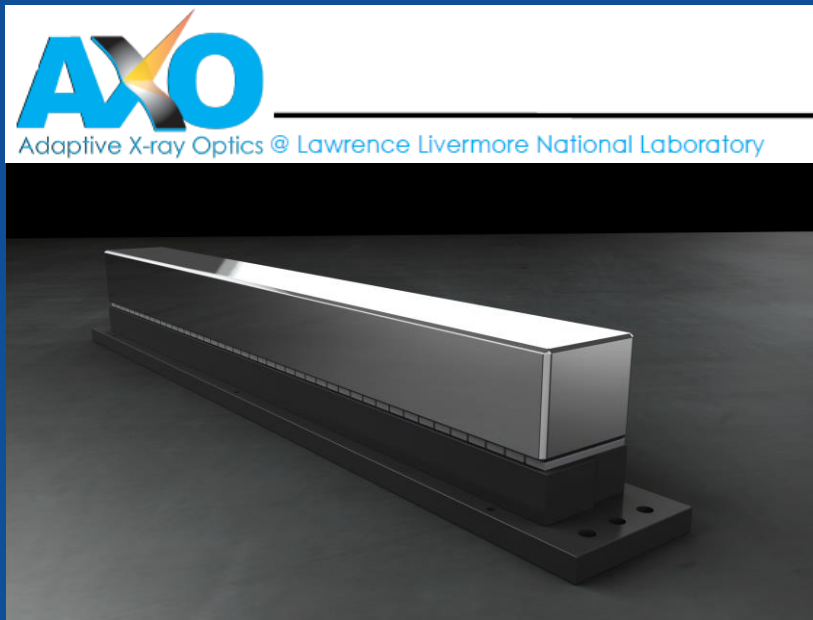
Metrology status

- Investigating well-established methods
 - Ptychography
 - Shearing interferometry (IWXM 2015)

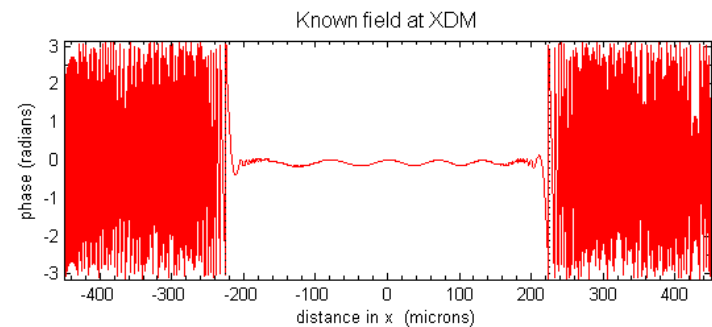
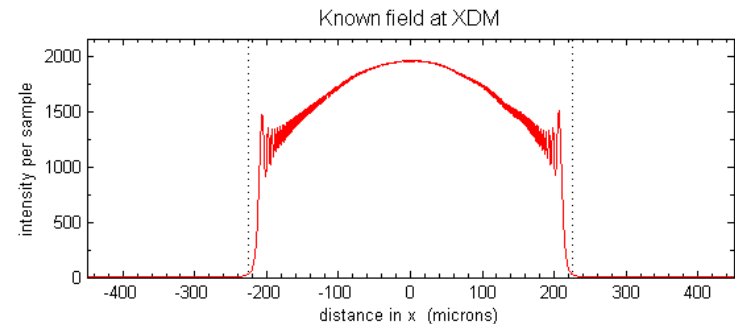
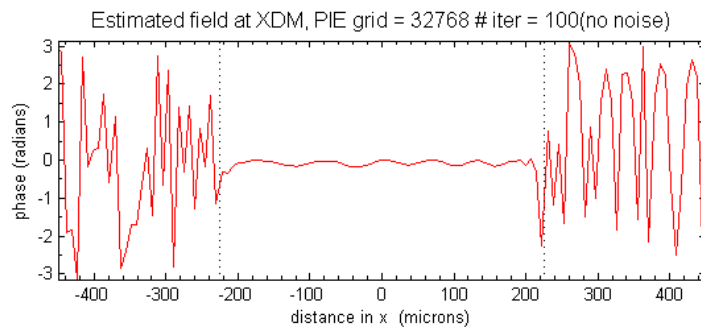
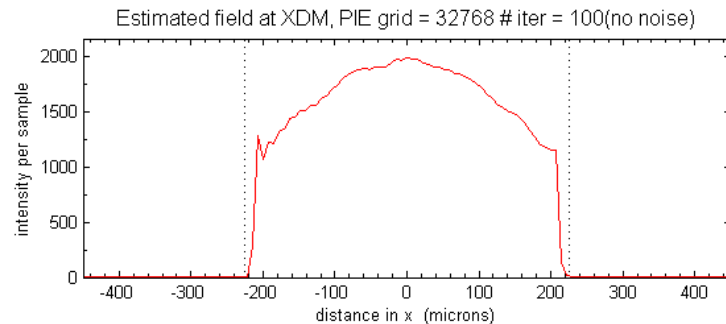


Metrology status - ptychography

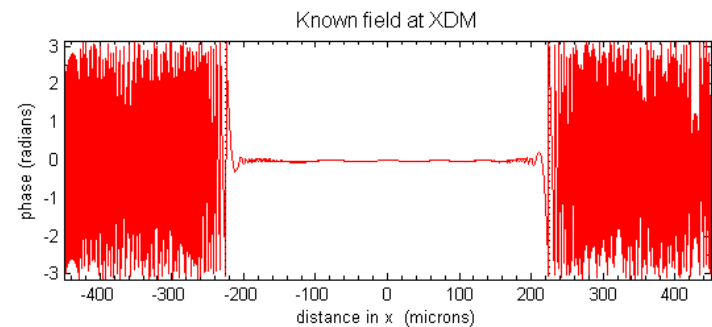
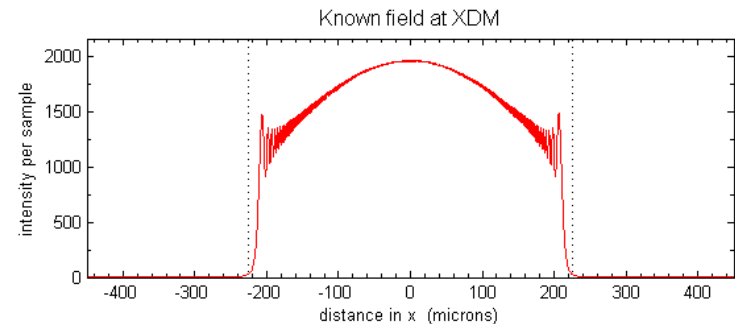
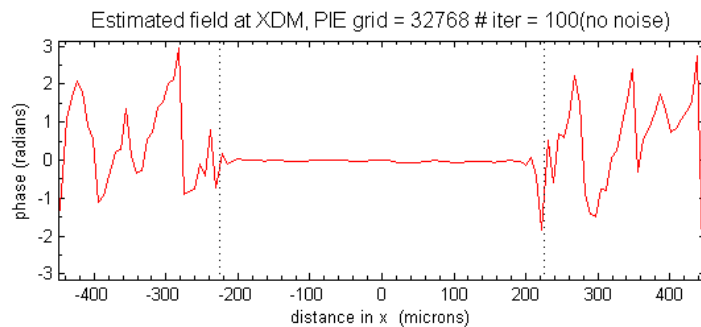
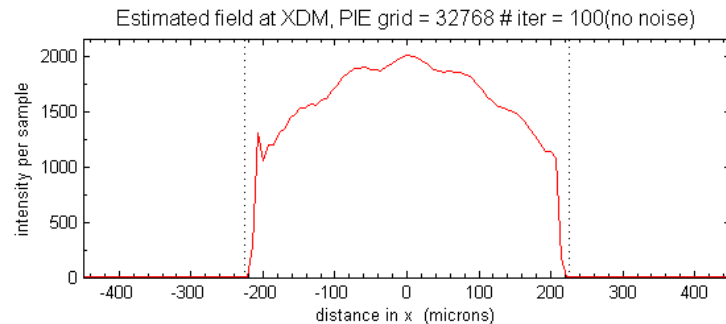




Metrology status – 3 nm ripple

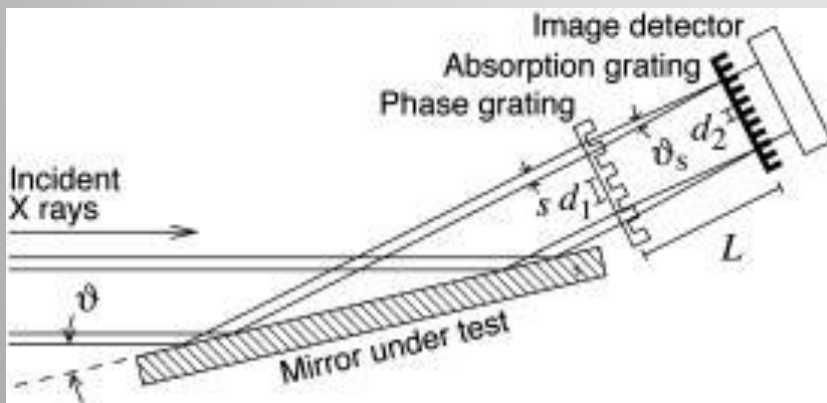


Metrology status – 1 nm ripple



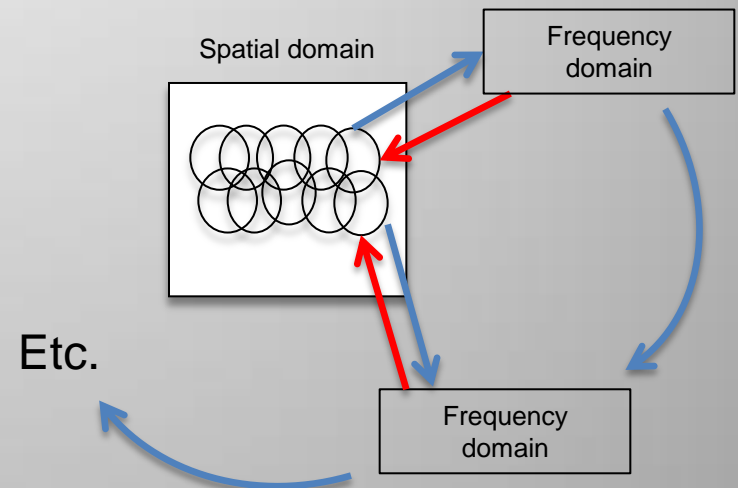
Metrology

Shearing interferometer

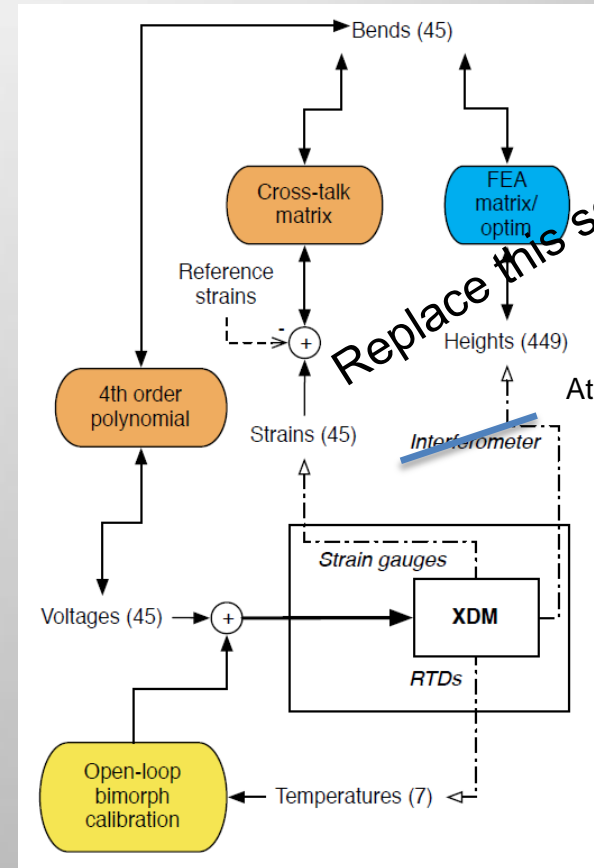
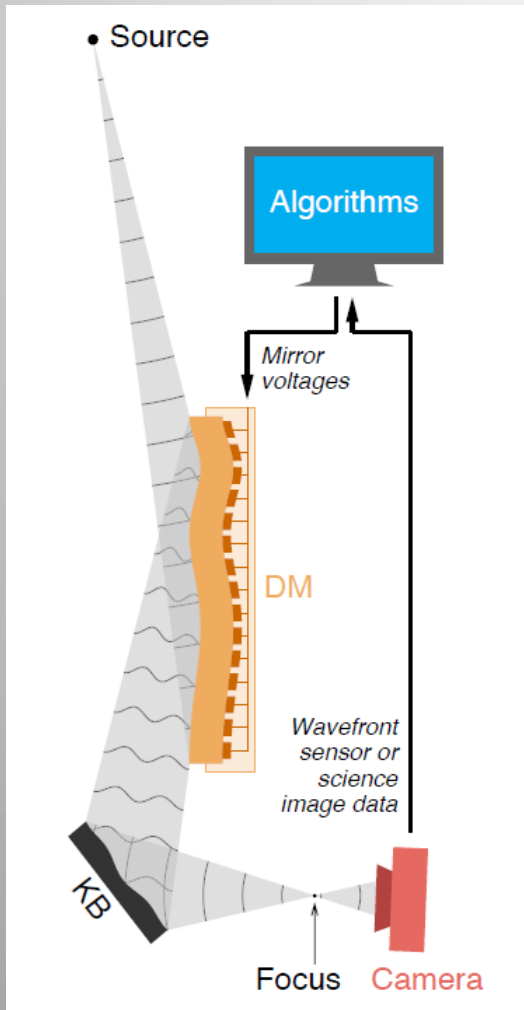


T. Weitkamp et al.,
Appl. Phys. Lett. **86**, 054101 (2005)

Ptychography



Closing the loop, at-wavelength



Replace this segment with